

Complete Set of Claims

- 1.(currently amended) A fine pattern forming material comprising a water-soluble resin, a water-soluble crosslinking agent, and a solvent consisting of water or a mixed solvent of water and a water-soluble organic solvent, ~~characterized in that the above fine pattern forming material comprises and~~ an amine compound which is at least one selected from the group ~~consisting~~ of a primary amine compound selected from a group of hydrazine, urea, amino acid, a glucosamine derivative and a polyallylamine derivative, where the an amino group of which the polyallylamine is partially protected at least by one selected from the group ~~consisting~~ of an alkyloxycarbonyl group, an aryloxycarbonyl group and an alkylcarbonyl group, and a quaternary amine compound ~~thereof consisting selected from a group~~ of dimethylammonium salt, trimethylammonium salt, tetramethylammonium salt, dimethylethylbenzylammonium salt and N-methylpyridinium salt and that pH value of the ~~above~~ fine pattern forming material exceeds 7.0.
- 2.(currently amended) The fine pattern forming material according to claim 1 wherein the ~~above~~ water-soluble resin is at least one selected from ~~the a~~ group ~~consisting~~ of a polyvinylalcohol derivative, a polyvinylpyrrolidone derivative and a polyacrylic acid derivative.
- 3.(currently amended) The fine pattern forming material according to claim 1 ~~or 2~~, wherein the above amine compound is a polyallylamine derivative having the molecular weight of 1,000 to 10,000.
- 4.(currently amended) The fine pattern forming material according to ~~any one of claims 1 to 3~~ further comprising a surfactant.

5.(currently amended) The fine pattern forming material according to claim 4, wherein the above surfactant is at least one selected from the group consisting of an anionic surfactant consisting selected from a group of alkylsulfonate, alkylbenzene sulfonic acid and alkylbenzenesulfonate, a cationic surfactant consisting selected from a group of laurylpolyidinium chloride and laurylmethylammonium chloride and a nonionic surfactant consisting selected from a group of polyoxyethylene octylether, polyoxyethylene laurylether and polyoxyethylene acetylenic glycolether.

6.(currently amended) A fine pattern forming method which is characterized in comprising a step of forming a resist pattern made of a photoresist on a substrate, a step wherein a coating layer is formed by applying the fine pattern forming material described in any one of claims 1 to 5 over the resist pattern, a step wherein the area neighboring to a the resist pattern is crosslinked and/or cured by heating the before-described resist pattern and the before-described coated layer and caused by a diffusion of an acid from the resist pattern, and a step wherein the before-described coated layer is developed by water or a mixture of water and a water-soluble organic solvent after heating.

7.(new) The fine pattern forming material according to claim 1 where water-soluble crosslinking agent is at least one selected from the group consisting of a melamine derivative and a urea derivative.

8.(new) The fine pattern forming material according to claim 1 where organic solvent is at least one selected from a group of alcohols, ketones, esters, ethylene glycol monoalkylethers, ethylene glycol monoalkylether acetates, propylene glycol monoalkylethers, propylene glycol monoalkylether acetates, lactic esters, aromatic hydrocarbons, amides, lactones, aprotic polar

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solvents.

9.(new) The fine pattern forming material according to claim 1, further comprising a plasticizer.

10.(new) The fine pattern forming material according to claim 4, further comprising a plasticizer.

11.(new) The method of claim 6, where the curing temperature is in the range of about 90°C to about 130°C.

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